

ABSTRACT OF THE DISCLOSURE

A method of using PFCs recovered from the effluent of a CVD chamber cleaning

5 process as an influent for the cleaning process is provided which includes the steps of
selecting a first PFC gas mixture having a first ratio of C_2F_6 to CF_4 , providing the first
PFC gas mixture as the influent gas to the CVD chamber to create a CVD chamber
effluent gas of a second PFC gas mixture having a second ratio of C_2F_6 to CF_4 , adding
virgin C_2F_6 or CF_4 to the CVD chamber effluent gas in sufficient quantity to create a third
10 PFC gas mixture having the first ratio of C_2F_6 to CF_4 , and using the third PFC gas
mixture as the influent gas to the CVD chamber.

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